## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)
Takako YAMAGUCHI et al.	: Examiner: J. G. Jelsma )
Application No.: 10/529,891	: Group Art Unit: 1795
Completion of Entry into U.S. National	: Confirmation No.: 7802
Stage Under 35 U.S.C. § 371(c): July 26, 2005	, :
For: EXPOSURE MASK, METHOD OF DESIGNING	) :
AND MANUFACTURING THE SAME, EXPOSURE METHOD AND APPARATUS.	) ·
PATTERN FORMING METHOD, AND DEVICE MANUFACTURING METHOD	) June 22, 2009 : (Monday)

## Mail Stop RCE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

## AMENDMENT

Sir:

Prior to further examination on the merits, please amend the above-identified application as follows: